

Electronic supplementary information

Variable-valence ion and heterointerface accelerated electron transfer kinetics of electrochemical water splitting

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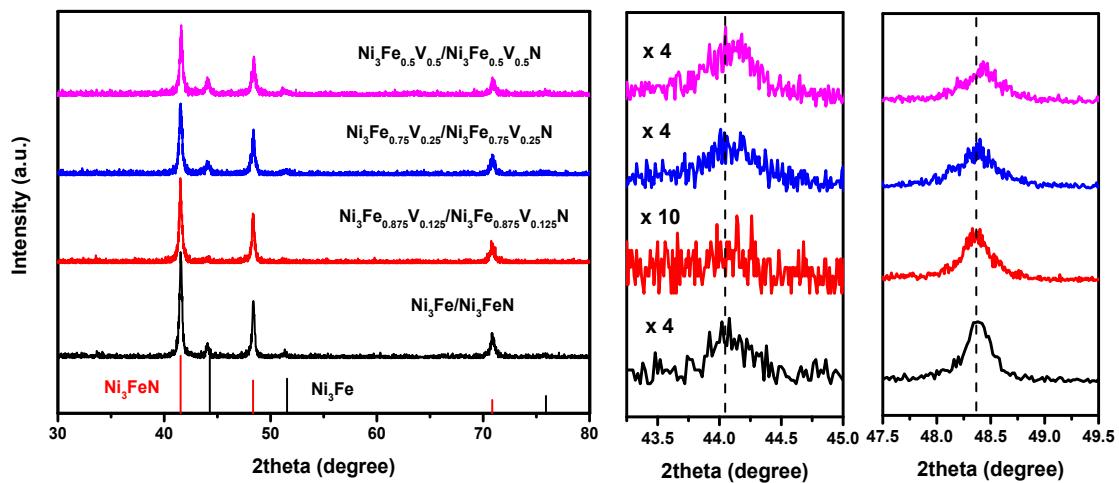


Fig. S1 XRD patterns of $\text{Ni}_3\text{Fe}_{1-x}\text{V}_x/\text{Ni}_3\text{Fe}_{1-x}\text{V}_x\text{N}$ ($x = 0, 0.125, 0.25, 0.5$) heterojunctions and enlarged regions at the 2theta of 43.25-45 and 47.5-49.5 degrees.

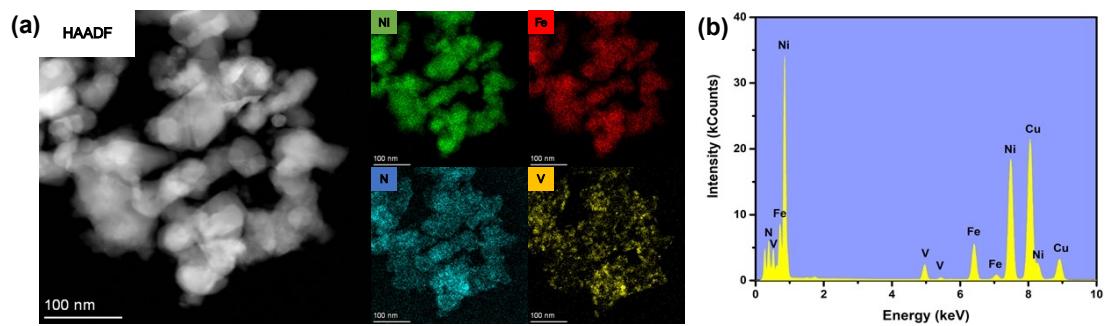


Fig. S2 (a) HAADF-STEM and (b) EDS elemental mapping images of $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$.

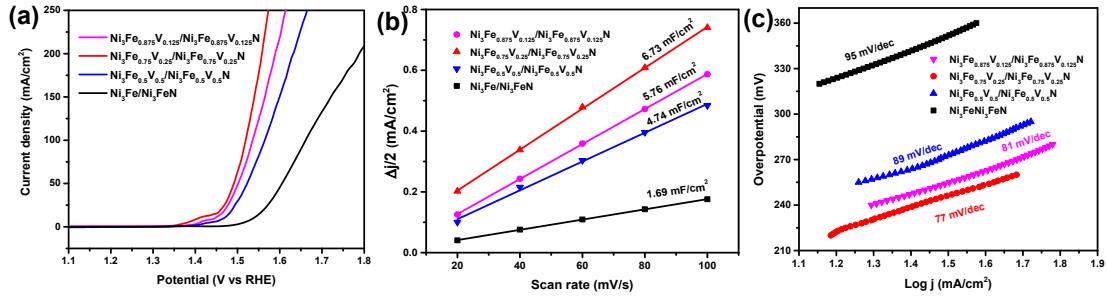


Fig. S3 The OER performances of $\text{Ni}_3\text{Fe}_{1-x}\text{V}_x/\text{Ni}_3\text{Fe}_{1-x}\text{V}_x\text{N}$ ($x = 0, 0.125, 0.25, 0.5$). (a) OER polarization curves with 90 % iR correction at a scan rate of 10 mV/s in 1.0 M KOH. (b) Plots of capacitive current density versus scan rate. The slopes (C_{dl}) represent ECSAs. (c) Tafel plots derived from the LSV data.

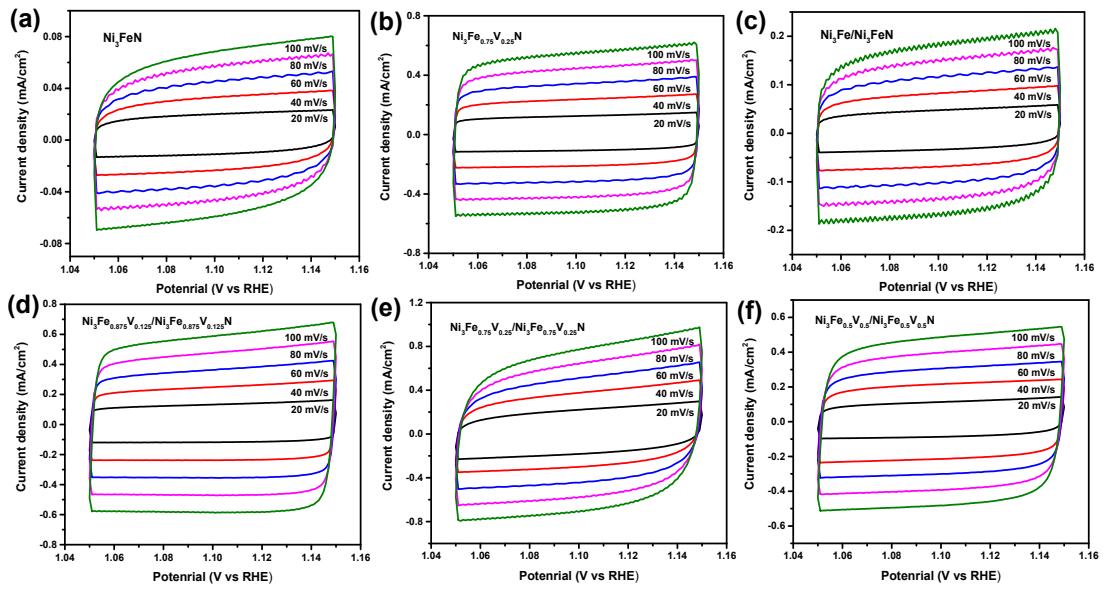


Fig. S4 Cyclic voltammetry curves of (a) Ni_3FeN , (b) $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$, (c) $\text{Ni}_3\text{Fe}/\text{Ni}_3\text{FeN}$, (d) $\text{Ni}_3\text{Fe}_{0.875}\text{V}_{0.125}/\text{Ni}_3\text{Fe}_{0.875}\text{V}_{0.125}\text{N}$, (e) $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$, and (f) $\text{Ni}_3\text{Fe}_{0.5}\text{V}_{0.5}/\text{Ni}_3\text{Fe}_{0.5}\text{V}_{0.5}\text{N}$ at various scan rates (20, 40, 60, 80 and 100 mV/s) in 1.0 M KOH.

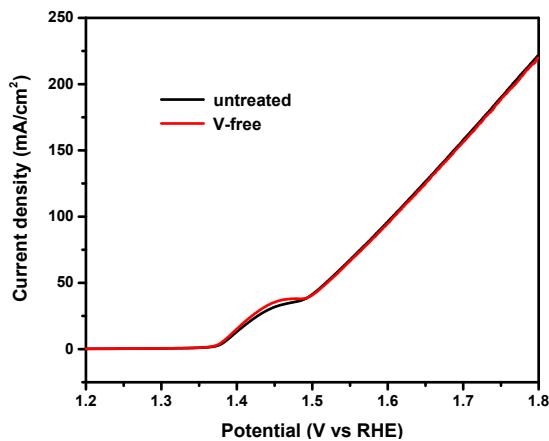


Fig. S5 The OER activities of $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$ tested without iR correction in 1.0 M KOH solution with and without dissolved V ions.

To address the V-effect, the equal amount of fresh 1.0 M KOH solution was substituted after activating the samples, which was labeled as V-free. It can be seen from Fig. S5 that the activated $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$ shows indistinguishable LSV curves for OER, indicating that the trace amount of dissolved V ions barely affected the assessment of electrocatalytic activities.

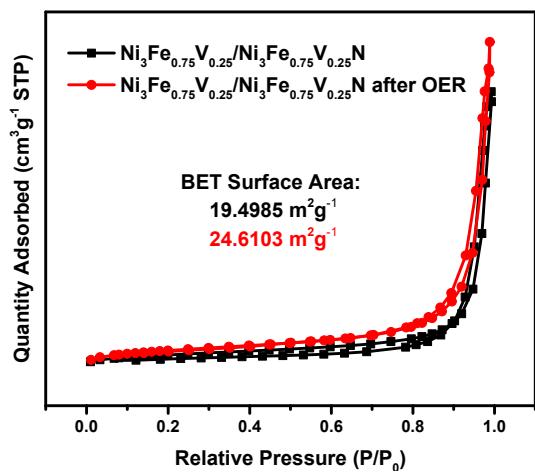


Fig. S6 N₂ adsorption-desorption isotherms and Brunauer-Emmett-Teller (BET) specific surface areas of Ni₃Fe_{0.75}V_{0.25}/Ni₃Fe_{0.75}V_{0.25}N before and after OER.

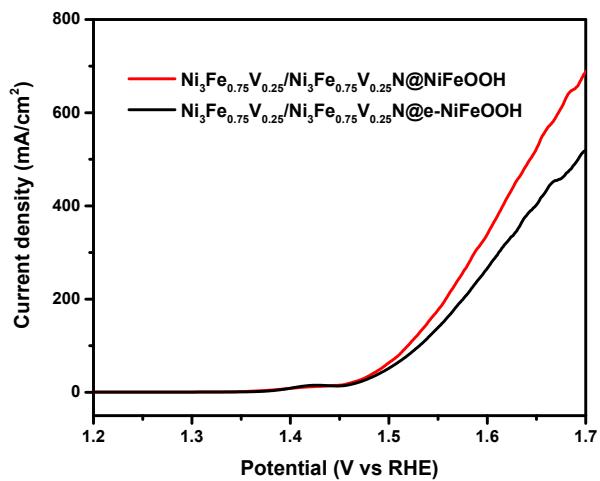


Fig. S7 The OER polarization curves of $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$ with in-situ formed FeNi (oxy)hydroxide ($\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}@\text{NiFeOOH}$) and electrodeposited FeNi (oxy)hydroxide ($\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}@e\text{-NiFeOOH}$).

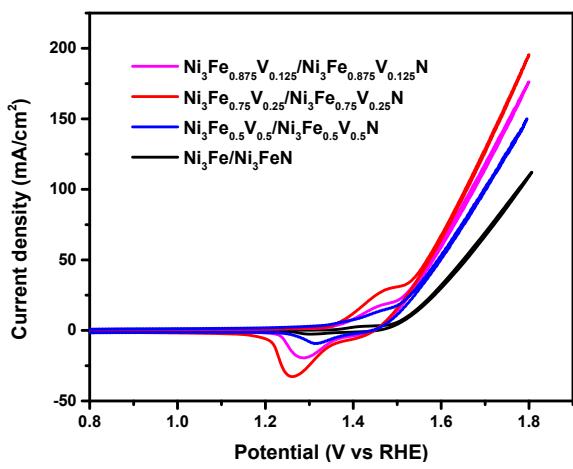


Fig. S8 CV curves of $\text{Ni}_3\text{Fe}_{1-x}\text{V}_x/\text{Ni}_3\text{Fe}_{1-x}\text{V}_x\text{N}$ ($x = 0, 0.125, 0.25, 0.5$) in 1.0 M KOH with a scan rate of 100 mV/s without iR compensation.

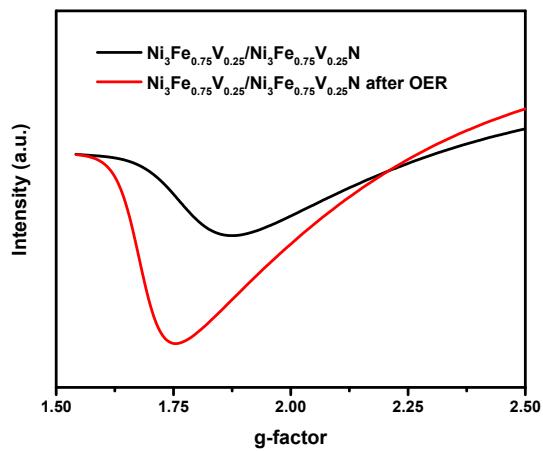


Fig. S9 The EPR spectra of $\text{Ni}_3\text{Fe}_{0.875}\text{V}_{0.125}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$ before and after OER.

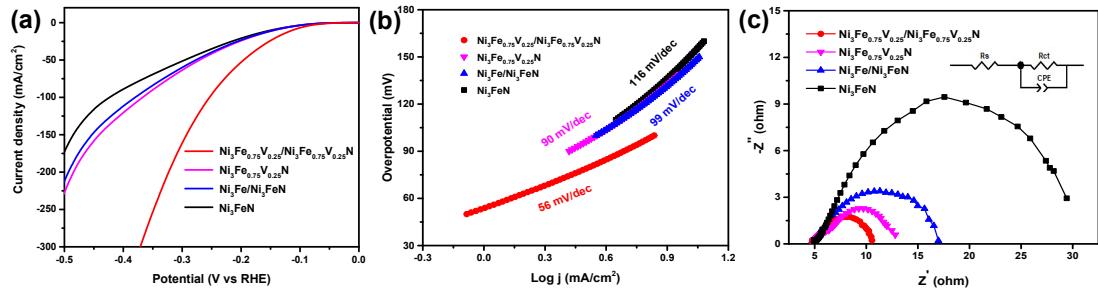


Fig. S10 The performances and properties of Ni₃FeN, Ni₃Fe_{0.75}V_{0.25}N, Ni₃Fe/Ni₃FeN, and Ni₃Fe_{0.75}V_{0.25}/Ni₃Fe_{0.75}V_{0.25}N for HER. (a) HER polarization curves with 90% iR correction at a scan rate of 10 mV/s in 1.0 M KOH. (b) Tafel plots derived from the LSV data. (c) EIS Nyquist plots.

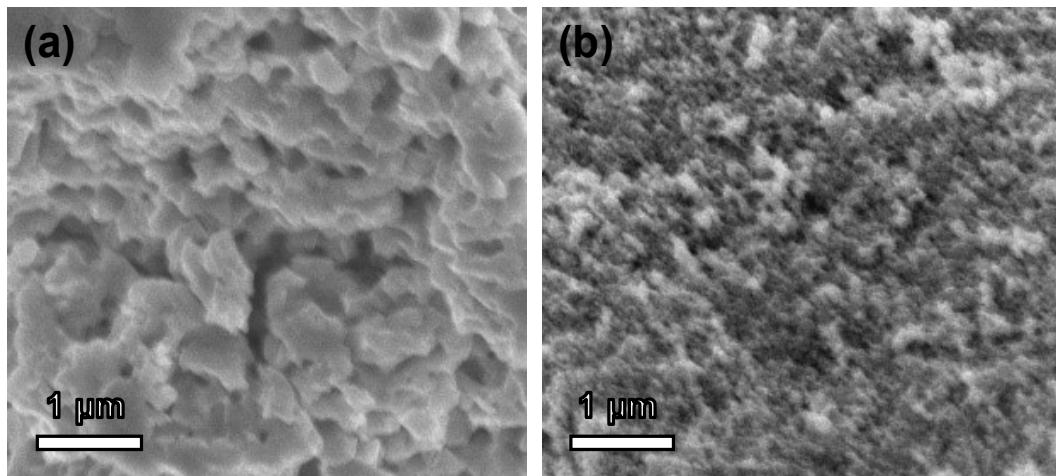


Fig. S11 SEM images of (a) as-prepared $\text{Ni}_3\text{Fe}/\text{Ni}_3\text{FeN}$ and (b) $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$.

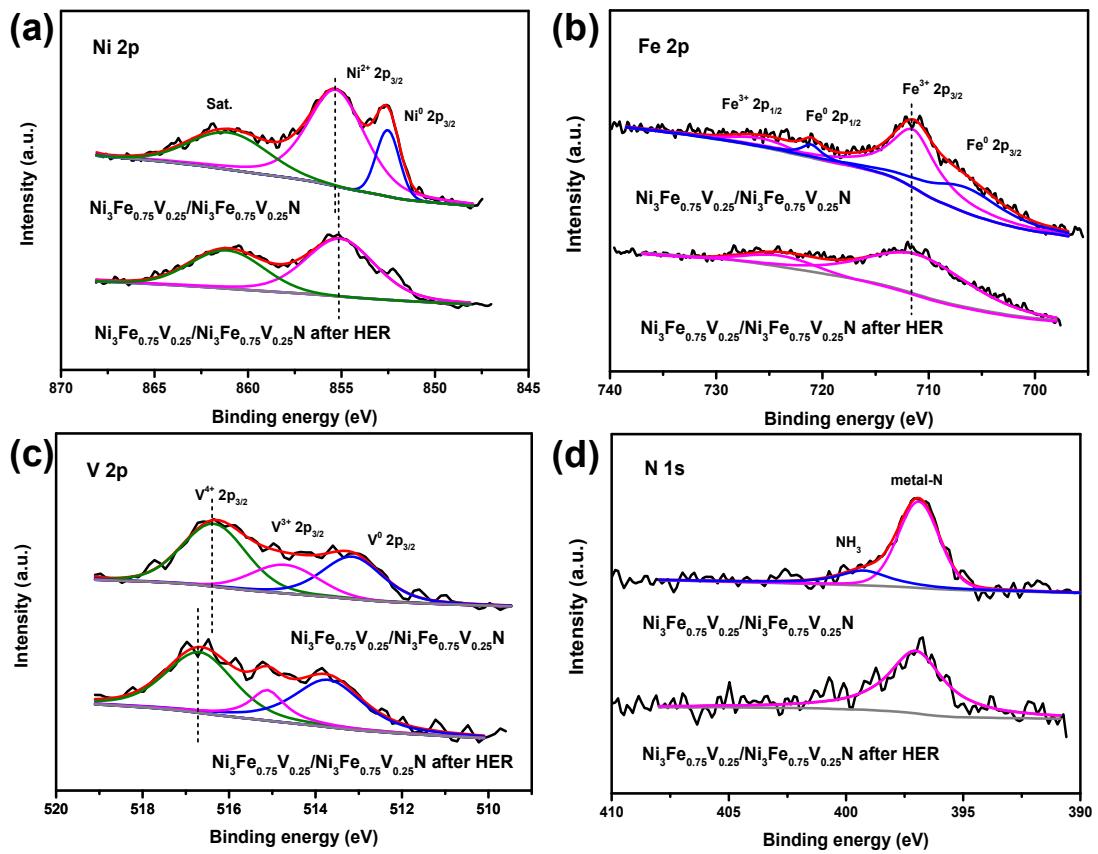


Fig. S12 XPS spectra of (a) Ni 2p, (b) Fe 2p, (c) V 2p and (d) N 1s for $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$

before and after HER.

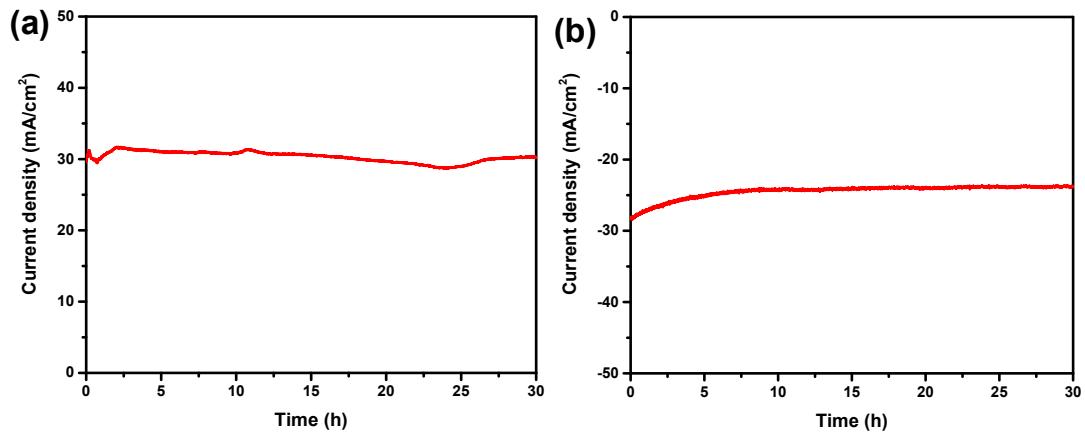


Fig. S13 Time-dependent stability of $\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}/\text{Ni}_3\text{Fe}_{0.75}\text{V}_{0.25}\text{N}$ for (a) OER and (b) HER at the applied potential of 1.5 V vs RHE and -0.3 V vs RHE, respectively.

Table S1 Compositions of the samples determined by ICP-AES.

Samples	The content of metal ions (mmol/L)			Mole ratio	
	Ni	Fe	V	Ni/(Fe+V)	V/Fe
Ni ₃ Fe/Ni ₃ FeN	5.844	1.987	/	2.94	/
Ni ₃ Fe _{0.75} V _{0.25} /Ni ₃ Fe _{0.75} V _{0.25} N	5.197	1.303	0.418	3.02	0.32
Ni ₃ Fe _{0.75} V _{0.25} /Ni ₃ Fe _{0.75} V _{0.25} N@NiFeOOH	4.481	1.067	0.129	3.75	0.12

Table S2 The OER and HER performances comparison of V-Ni₃Fe/Ni₃FeN with the alloy(metal)/nitrides composite electrocatalysts currently reported.

Samples	OER (mV)	HER (mV)	Reference
Ni ₃ Fe _{0.75} V _{0.25} /Ni ₃ Fe _{0.75} V _{0.25} N	261 (η_{50})	113 (η_{10})	this work
Ni ₃ Fe/Ni ₃ FeN	390 (η_{50})	166 (η_{10})	1
Ni ₃ Fe/Ni ₃ FeN	290 (η_{50})	--	2
Ni ₃ Fe/Ni ₃ FeN	295 (η_{50})	125 (η_{10})	3
Mo-Ni ₃ Fe/Ni ₃ FeN	340 (η_{50})	234 (η_{10})	4
Fe ₃ Pt/Ni ₃ FeN	365 (η_{10})	--	5
Ni/Ni ₃ FeN	255 (η_{50})	--	6
NiCu/NiCuN/NC	232 (η_{10})	93 (η_{10})	7
FeCo/Co ₄ N/NC	280 (η_{10})	--	8
WC/W ₂ N	320 (η_{10})	148.5 (η_{10})	9
Co ₃ W/WN	273 (η_{10})	43 (η_{10})	10
CoB _x @BN	290 (η_{10})	--	11

It was noted that the overpotential of Ni/Ni₃FeN@NiFeOOH reported in the reference 6 was a little smaller than the Ni₃Fe_{0.75}V_{0.25}/Ni₃Fe_{0.75}V_{0.25}N@NiFeOOH sample in this work, however, our catalysts presented much higher current density than Ni/Ni₃FeN@NiFeOOH at high potential.

Table S3 Fitting parameters of EIS plots for OER based on the Randle's equivalent circuit.

Samples	CPE/QPE		C _{ct} (mF)	R _{ct} (Ω)	R _s (Ω)
	P=n	T=Q ⁿ			
Ni ₃ FeN	0.86	1.6161	0.228	122.9	6.941
Ni ₃ Fe/Ni ₃ FeN	0.89	3.4247	0.956	30.35	6.953
Ni ₃ Fe _{0.75} V _{0.25} N	0.89	9.2408	3.297	16.49	7.167
Ni ₃ Fe _{0.875} V _{0.125} /Ni ₃ Fe _{0.875} V _{0.125} N	0.75	21.946	1.862	14.57	6.568
Ni ₃ Fe _{0.75} V _{0.25} /Ni ₃ Fe _{0.75} V _{0.25} N	0.76	67.172	13.01	5.972	5.532
Ni ₃ Fe _{0.5} V _{0.5} /Ni ₃ Fe _{0.5} V _{0.5} N	0.86	12.026	3.141	10.96	5.635

Table S4 Fitting parameters of EIS plots for HER based on the Randle's equivalent circuit.

Samples	CPE/QPE		C _{ct} (mF)	R _{ct} (Ω)	R _s (Ω)
	P=n	T=Q ⁿ			
Ni ₃ FeN	0.76	8.4979	0.420	26.24	5.531
Ni ₃ Fe/Ni ₃ FeN	0.63	14.344	0.048	12.78	5.056
Ni ₃ Fe _{0.75} V _{0.25} N	0.66	10.761	0.056	7.595	5.685
Ni ₃ Fe _{0.75} V _{0.25} /Ni ₃ Fe _{0.75} V _{0.25} N	0.67	18.577	0.228	5.821	5.115

The effective capacitance associated with the CPE can be calculated based on the equation:

$$C_{ct} = Q^{1/n} (1/R_s + 1/R_{ct})^{(n-1)/n}$$

where the parameters of pre-factor (Q) and exponent (n) are independent of frequency. When n=1, Q represents the capacity of the interface; when n<1, the system behavior is related to the surface heterogeneity ¹².

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